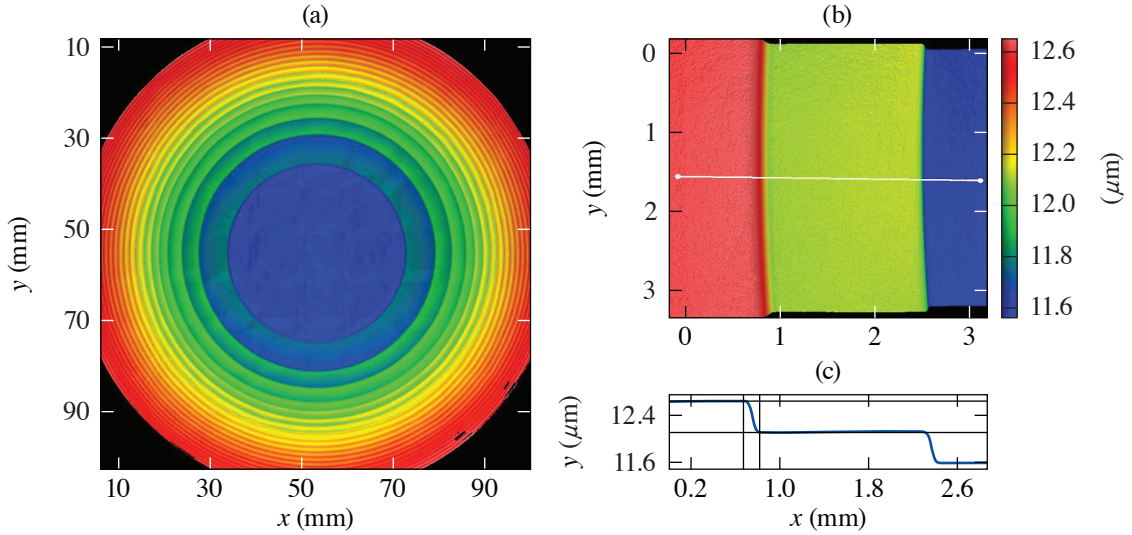
About the Cover:

The cover depicts the measured surface profile of a cylindrically symmetric echelon fabricated by electron-beam evaporation. A silicon dioxide monolayer is deposited through a discontinuous (stepped) mask profile to deposit a series of annular regions, each increasing in thickness by 0.53 μm from the center (0 thickness) to the edge of the 100-mm-diam substrate (thickness 12.1 μm). The surface profile was characterized by R. Boni using stitching white-light interferometry on a Zygo NexView.

The figure below exhibits the concentric nature of the echelon steps. Transitions between the individual steps of the echelon display a sloped sidewall of the order of 150 μm, the primary deviation from the ideal design with vertical sidewalls between steps.



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